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## SPIE appoints Chris Mack editor of 'Journal of Micro/Nanolithography, MEMS, and MOEMS'

**17 February 2011**

BELLINGHAM, Washington, USA -- SPIE has announced the appointment of renowned lithography expert [Chris A. Mack](#), adjunct faculty member at the University of Texas at Austin, as editor of the *Journal of Micro/Nanolithography, MEMS, and MOEMS*. The appointment is effective 1 January 2012.



The [Journal of Micro/Nanolithography, MEMS, and MOEMS](#) (JM3), founded in 2002, publishes peer-reviewed papers on the development of lithographic fabrication, packaging, and integration technologies necessary to address the needs of the electronics, microoptoelectromechanical systems, and photonics industries.

Mack will succeed JM3 founding editor [Burn Lin](#), Senior Director of Nanopatterning Technology, Taiwan Semiconductor Manufacturing Co.

"Since its founding, JM3 has become the preeminent journal in the various fields of microfabrication," Mack said. "I'm thrilled to be continuing the work of Burn Lin and to carry on the tradition of excellence at this journal."

"We are very pleased that Chris Mack has accepted the position of editor of JM3," said SPIE Publications Committee Chair [John Greivenkamp](#) (College of Optical Sciences, University of Arizona). "Dr. Mack is an internationally recognized expert in lithography who brings a wealth of knowledge, insight and enthusiasm that will be a great benefit to the journal and the entire technical community."

Mack received multiple undergraduate degrees from Rose-Hulman Institute of Technology, a master of science degree in electrical engineering from the University of Maryland, College Park, and a PhD in chemical engineering from the University of Texas.

He began working with lithography while at the Microelectronics Research Laboratory of the National Security Agency. After an assignment to Sematech, he left the NSA and founded FINLE Technologies to commercialize PROLITH, the simulator he had developed to model optical and chemical aspects of photolithography. FINLE Technologies was purchased in 2000 by KLA-Tencor, and Mack served as Vice President of Lithography Technology until 2005.

In addition to being on the faculty at the University of Texas at Austin, Mack frequently writes, teaches, and consults on semiconductor lithography.

Mack received the 2003 SEMI Award for North America for his efforts in lithography simulation and education, and in 2009 received the SPIE Frits Zernike Award for Microlithography.

The journal is published quarterly. For more information about the journal along with submission information for authors, see [www.SPIE.org/JM3](http://www.SPIE.org/JM3), or access the [Journal of Micro/Nanolithography, MEMS, and MOEMS](#) in the SPIE Digital Library.

[SPIE](#), the international society for optics and photonics, was founded in 1955 to advance light-based technologies. Serving more than 180,000 constituents from 168 countries, the Society advances emerging technologies through interdisciplinary information exchange, continuing education, publications,

patent precedent and career and professional growth. SPIE annually organizes and sponsors approximately 25 major technical forums, exhibitions and education programs in North America, Europe, Asia and the South Pacific, and supports scholarships, grants and other education programs around the world.

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